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ABSTRACT OF THE DISCLOSURE

1 A refractive projection objective for use in
2 microlithography with lenses made exclusively of one and the
3 same material has an image-side numerical aperture larger
4 than 0.7. A light bundle defined by the image-side
5 numerical aperture and by the image field has within the
6 objective a variable light-bundle diameter smaller than or
7 equal to a maximum light-bundle diameter. In a length
8 interval measured on the optical axis from the system
9 diaphragm towards the object field and at least equaling the
10 maximum light-bundle diameter, the variable light-bundle
11 diameter exceeds 85% of the maximum light-bundle diameter.